

10017262-121401

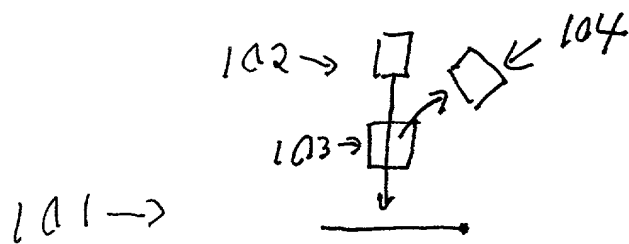


Figure 1

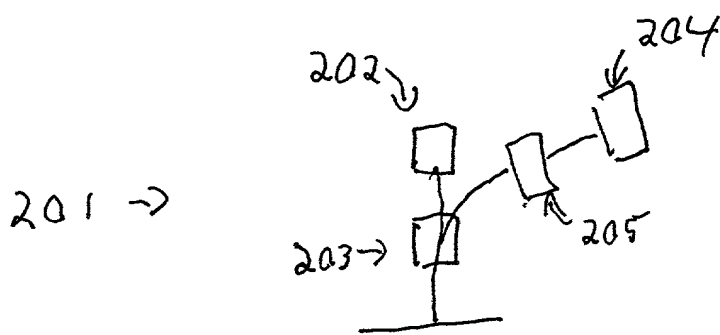
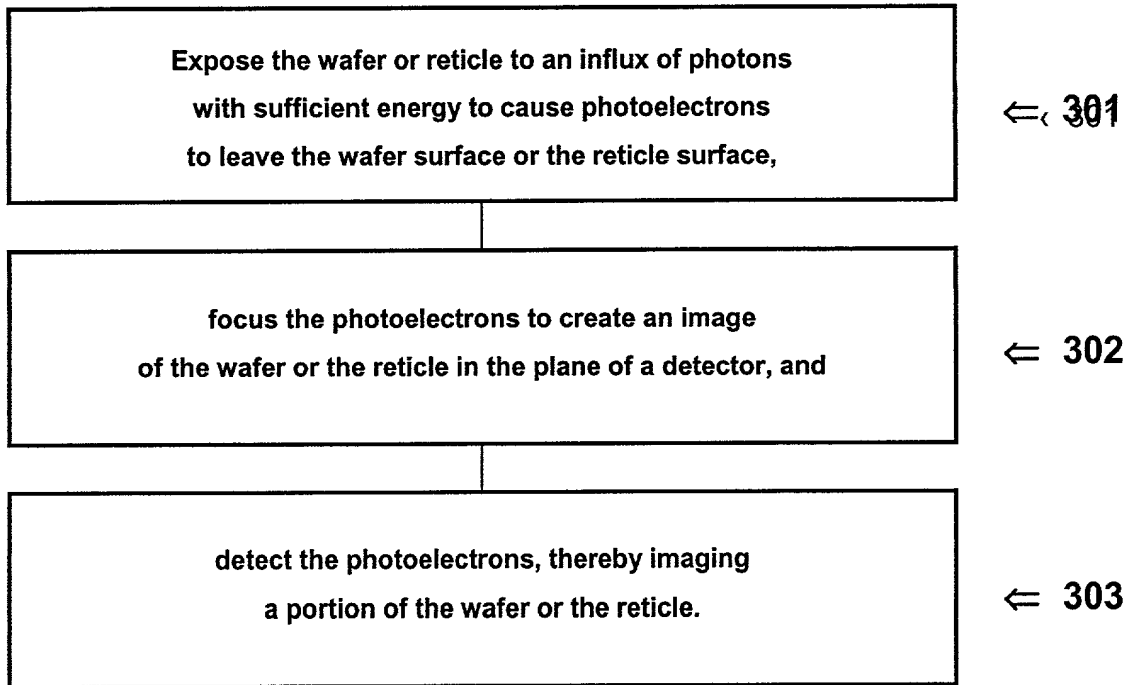
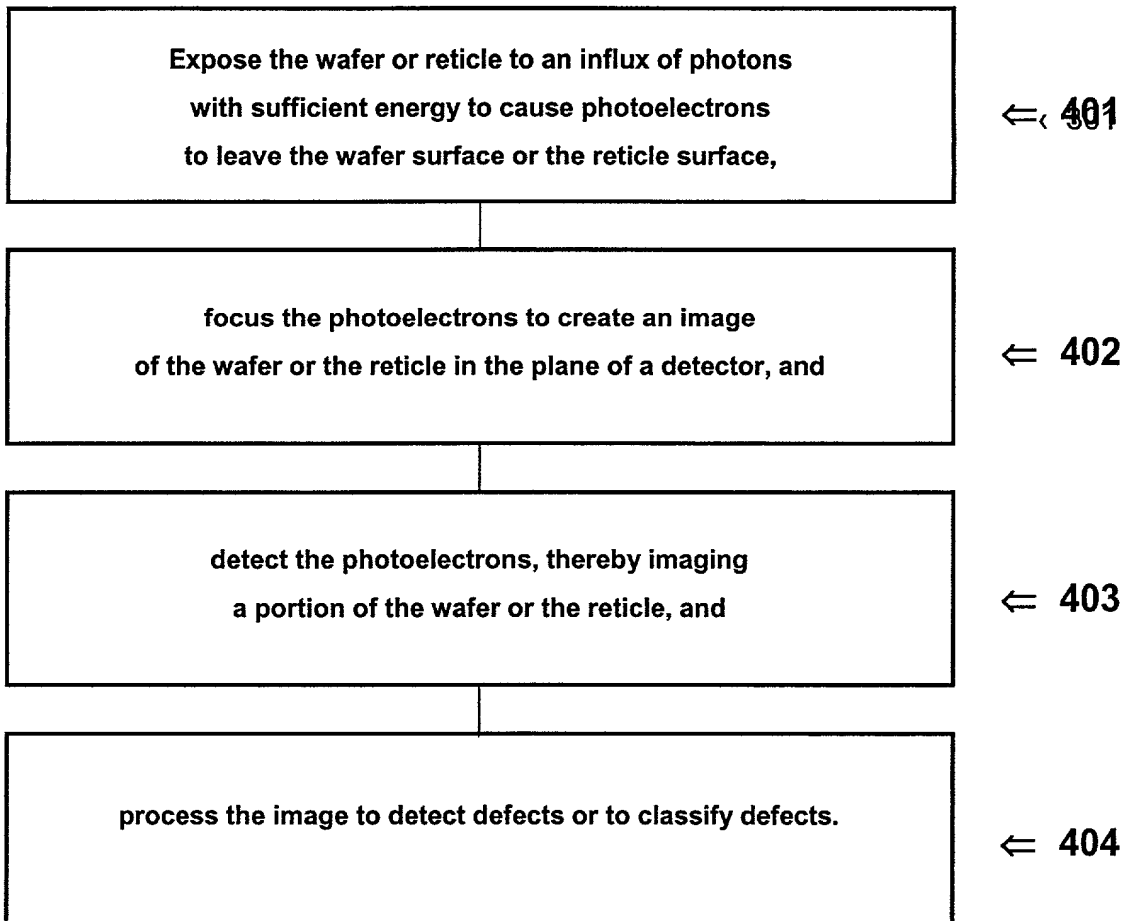


Figure 2



**Figure 3**



**Figure 4**

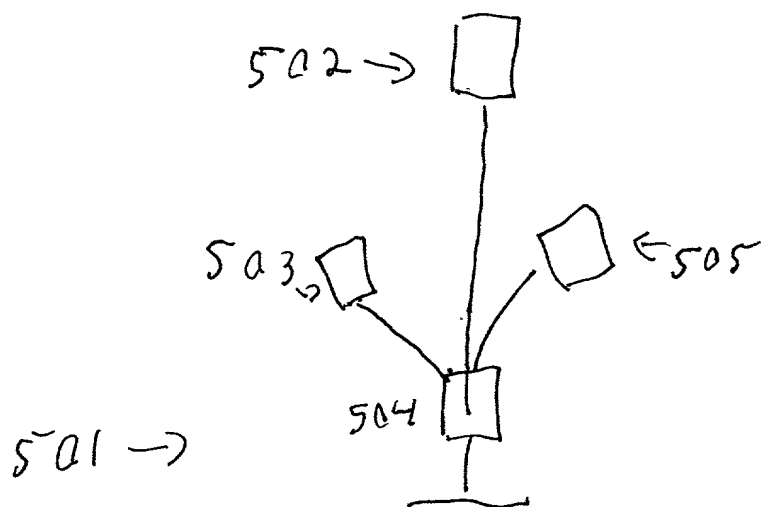


Figure 5

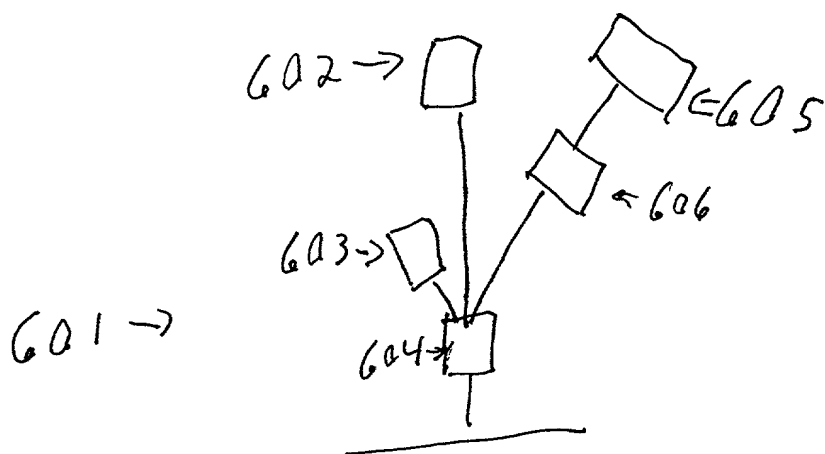


Figure 6

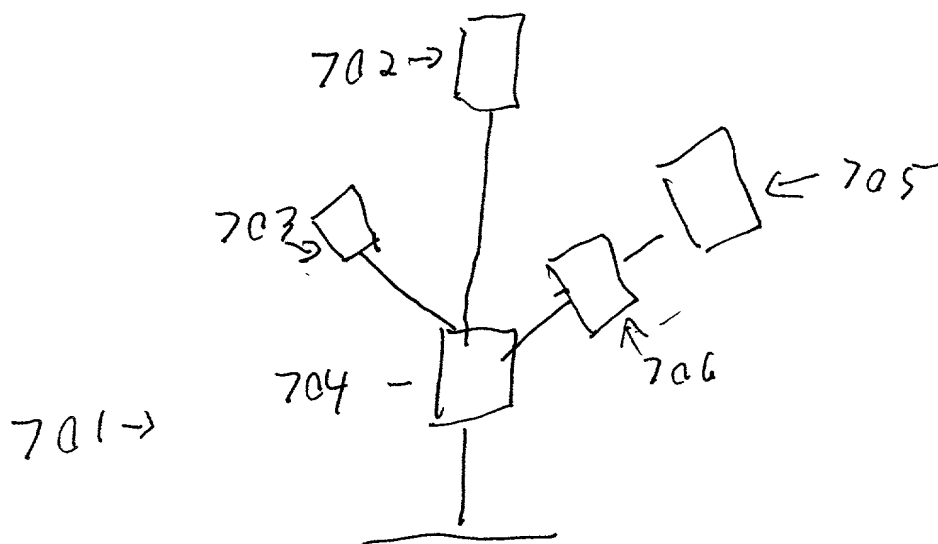


Figure 7

10017262-121401

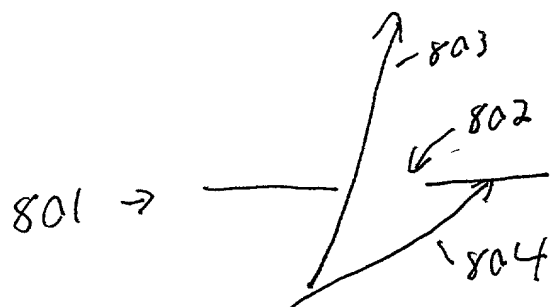


Figure 8



10017262-121401

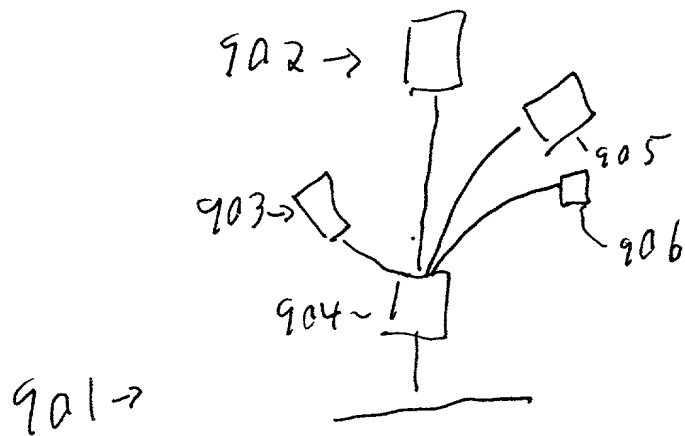


Figure 9

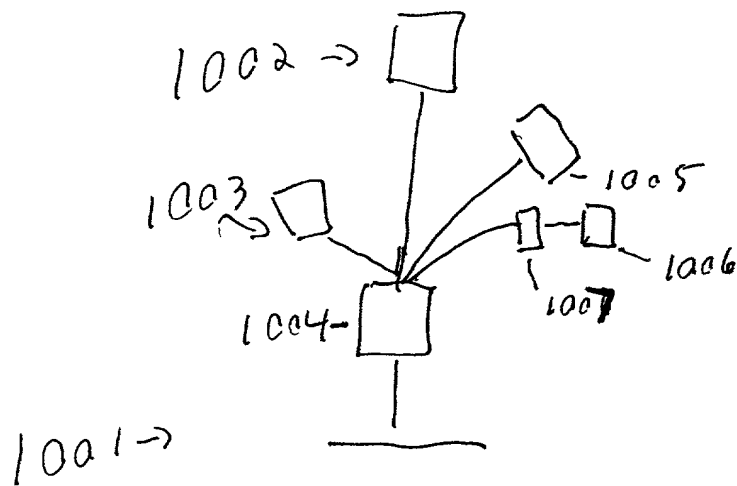


Figure 1a

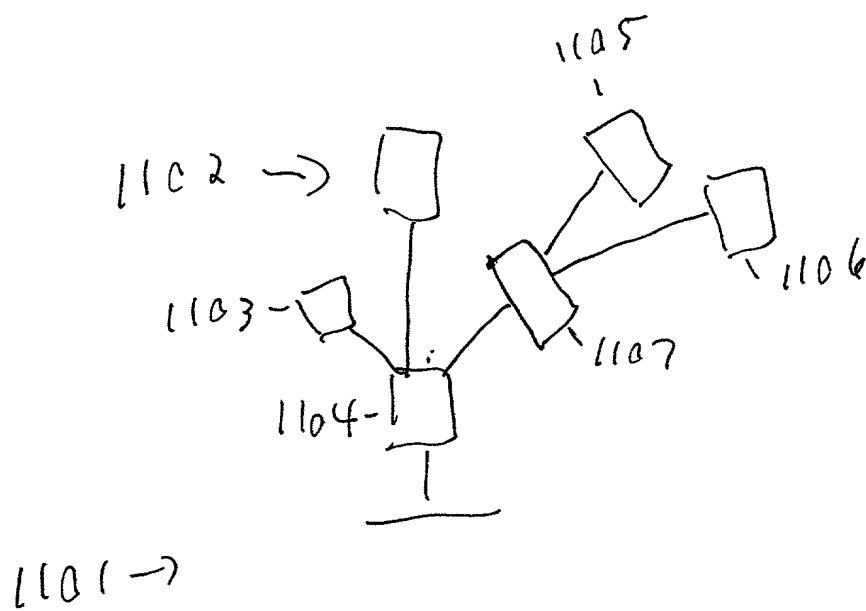


Figure 11



Figure 12

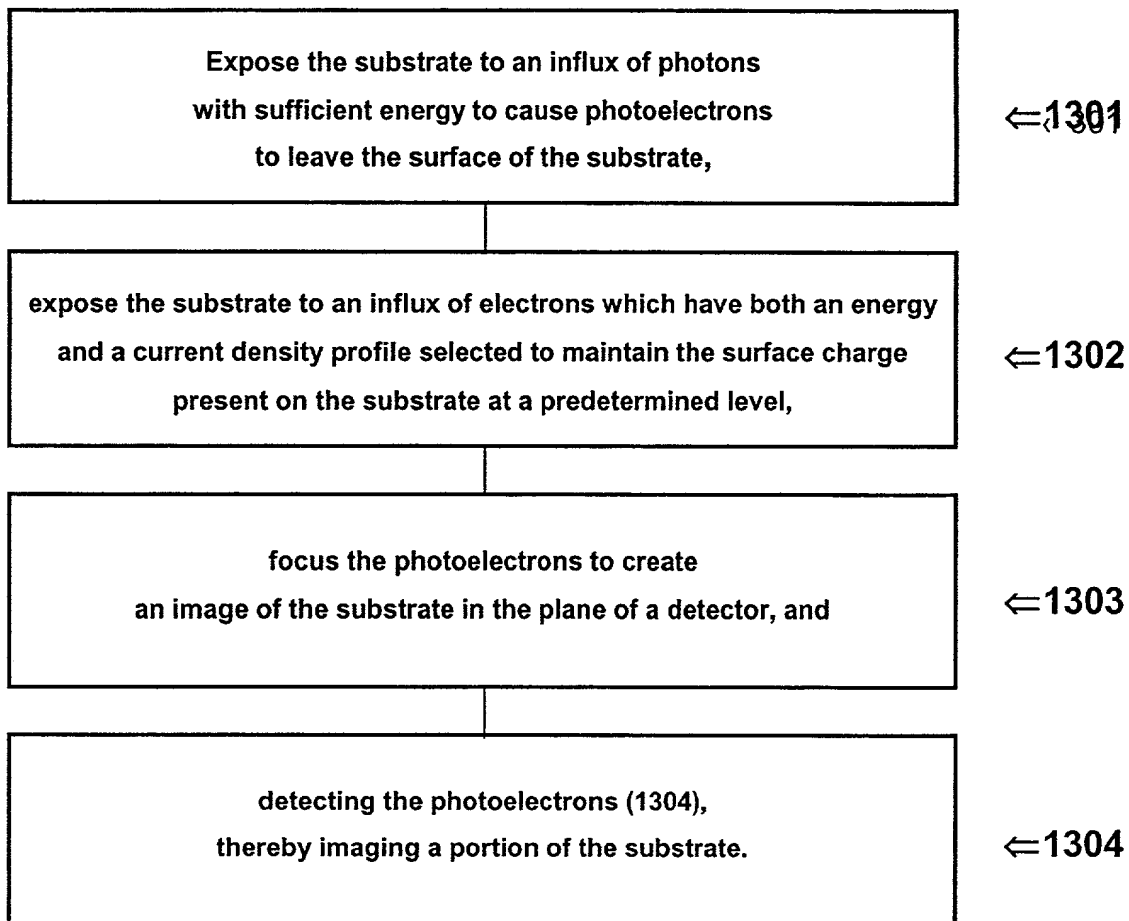


Figure 13

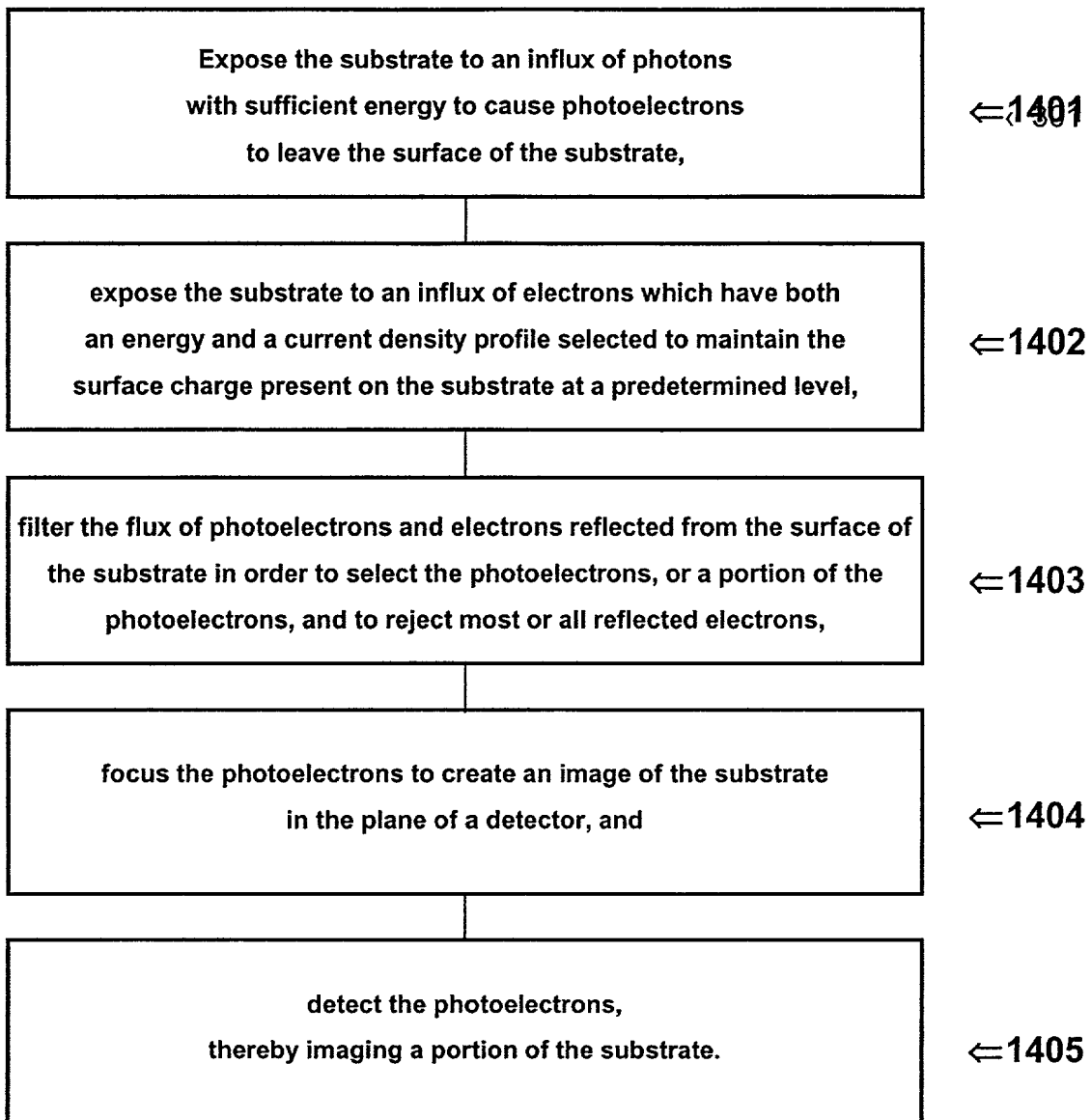
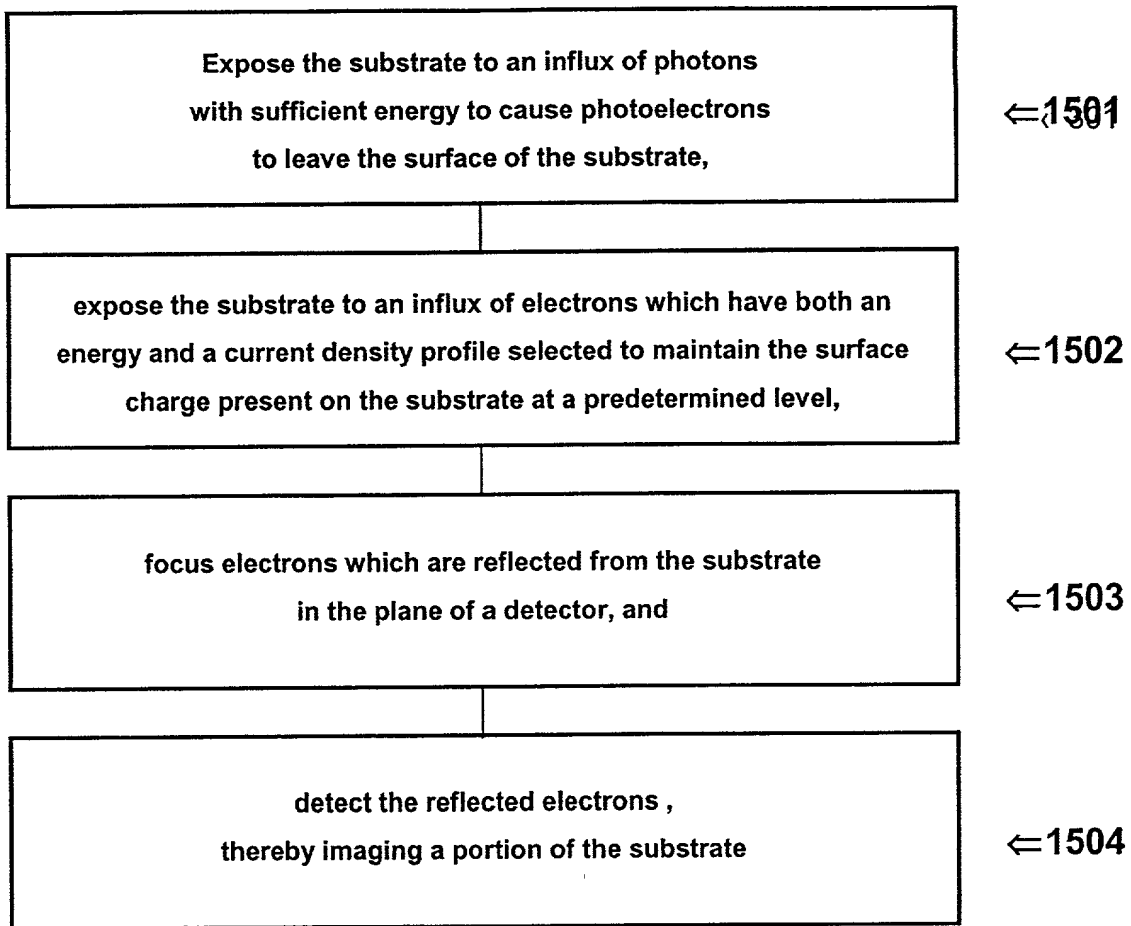


Figure 14



**Figure 15**

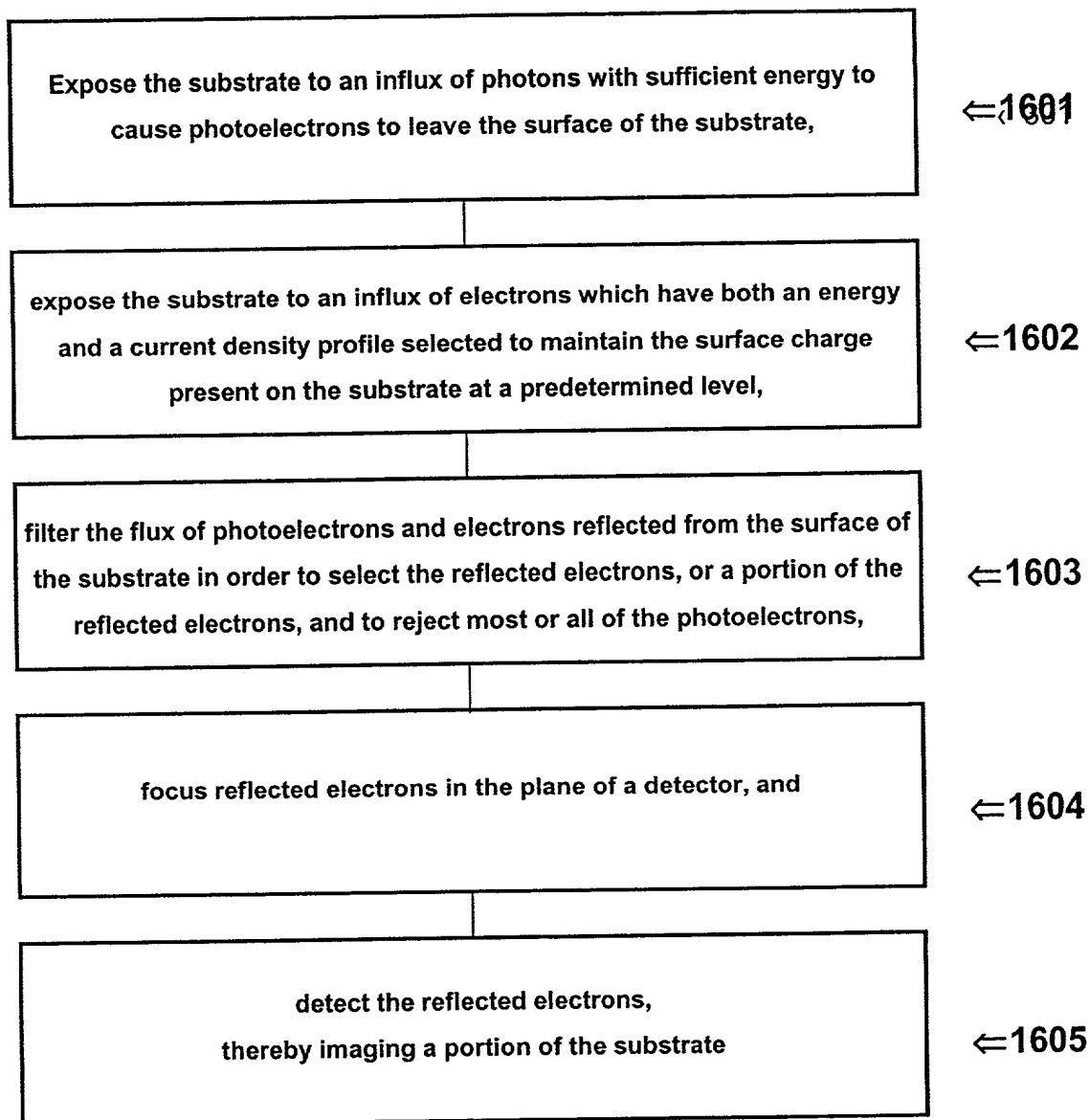
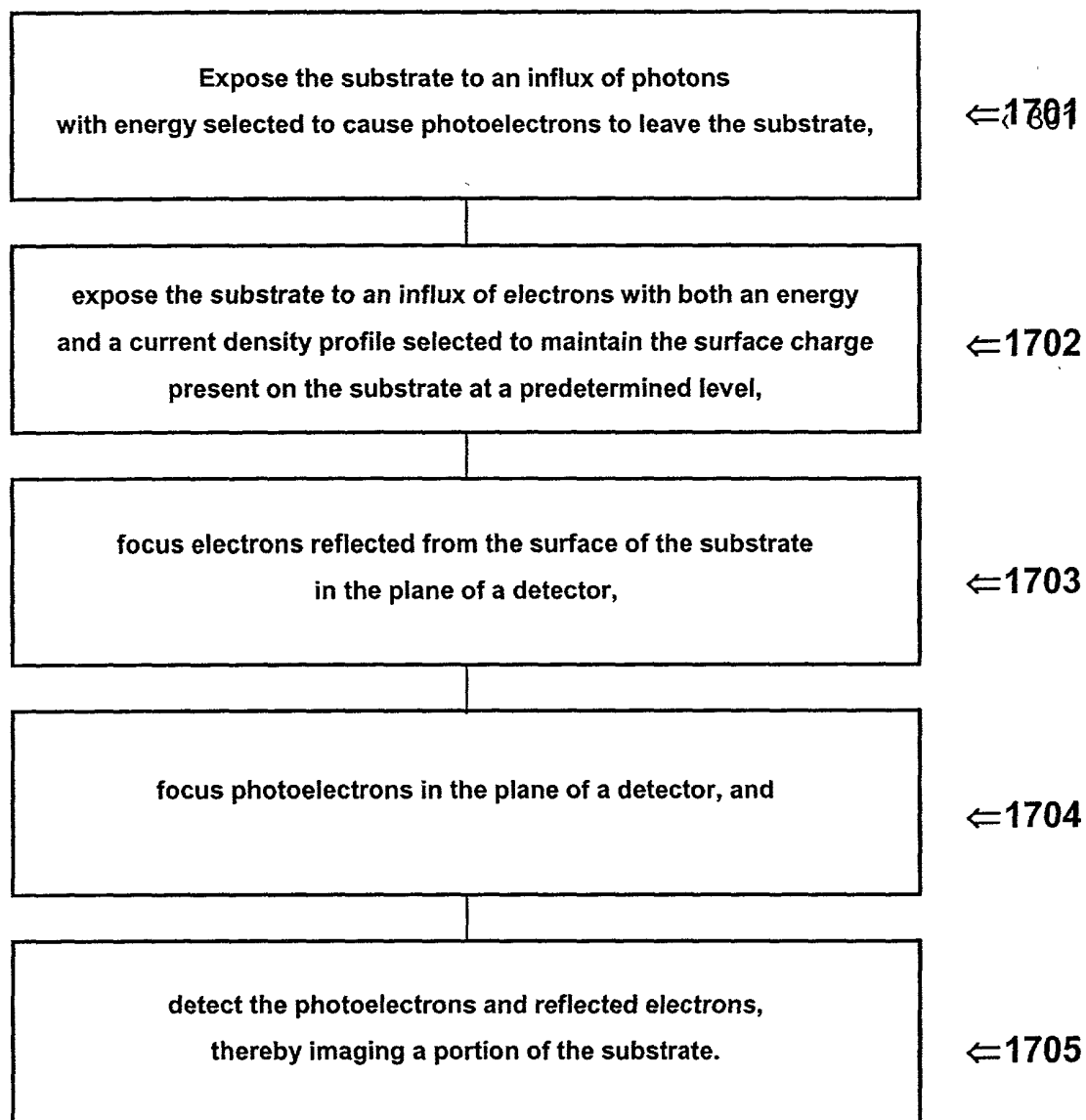


Figure 16





**Figure 17**

Expose the defect to an influx of photons with energy below the energy required to cause photoelectrons to leave the defect,

⇐1801

increase the energy of the photons in discrete steps,

⇐1802

monitor the photoelectron yield from the defect after each step, and,

⇐1803

identify the chemical composition of the defect on the basis of the photon energy at which the photoelectron yield increases substantially.

⇐1804

Figure 18

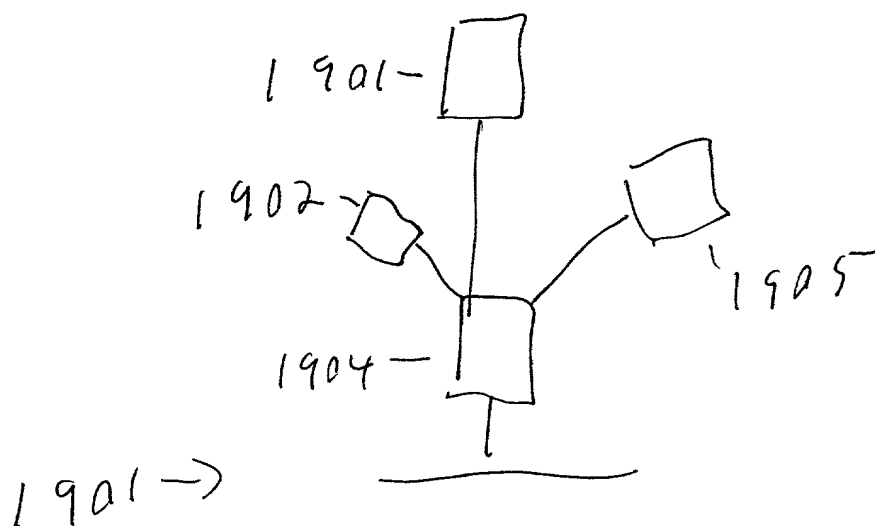


Figure 19

10017232-121401

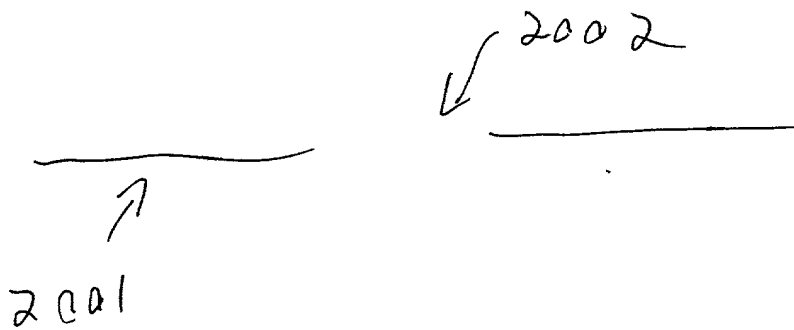
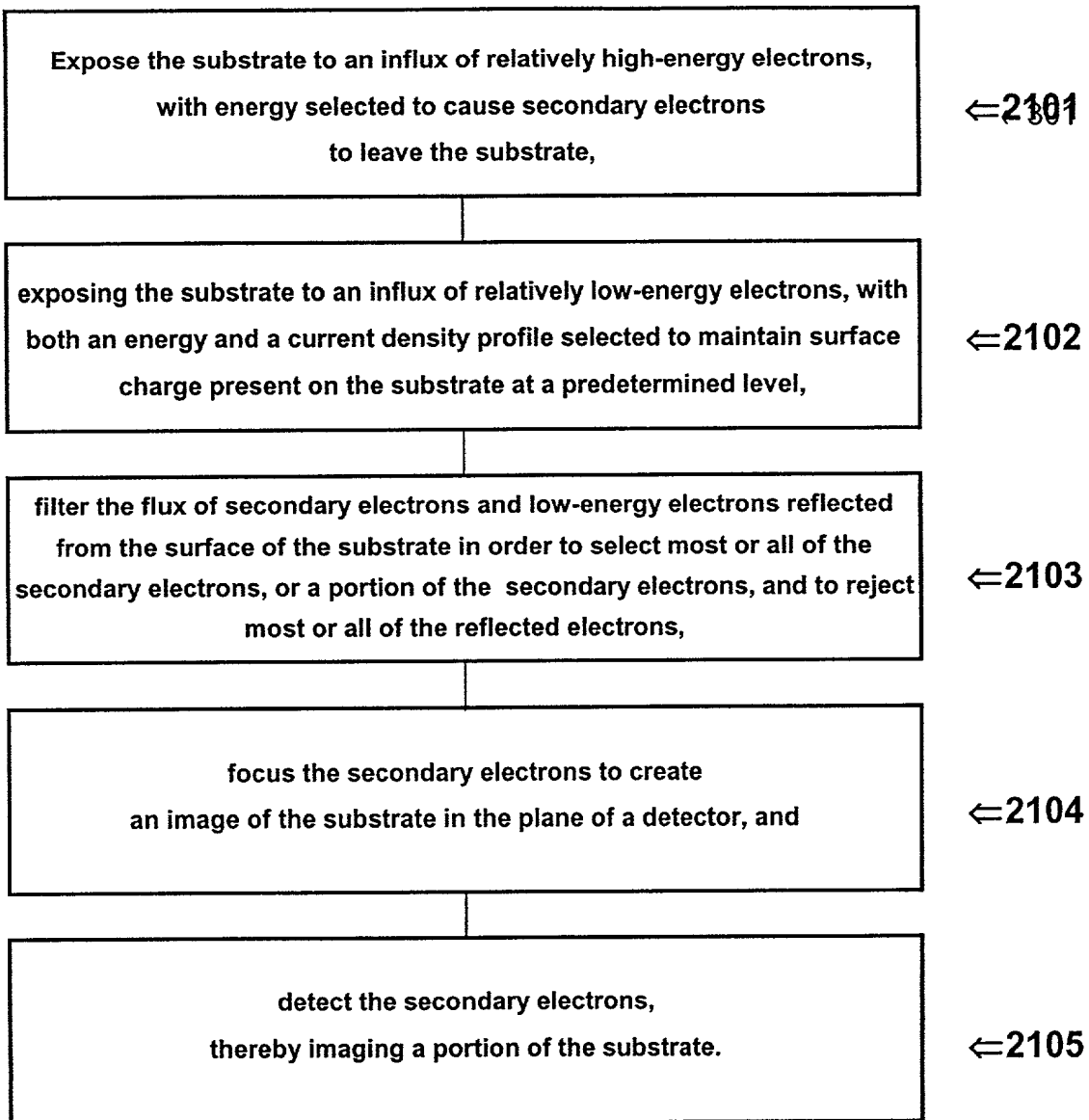
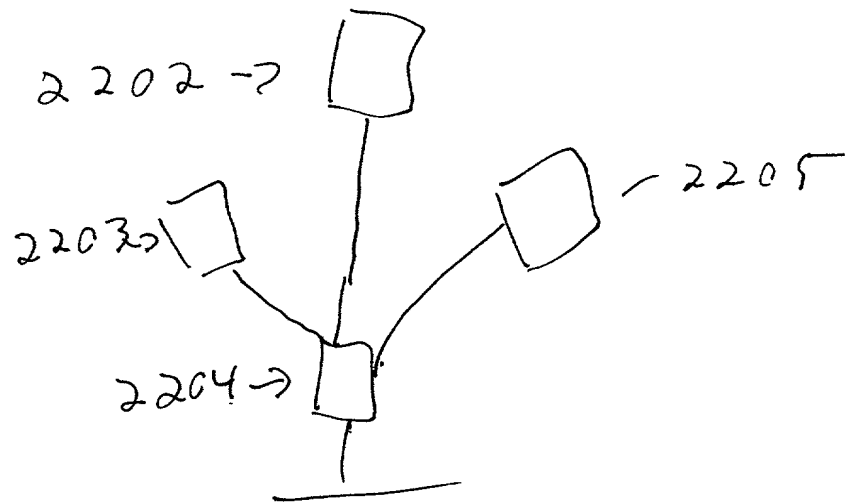


Figure 20




**Figure 21**



2201 ->

Figure 22

10017262 121401

2301 

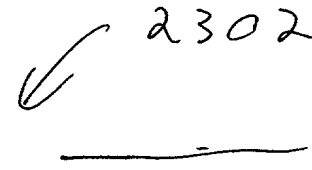
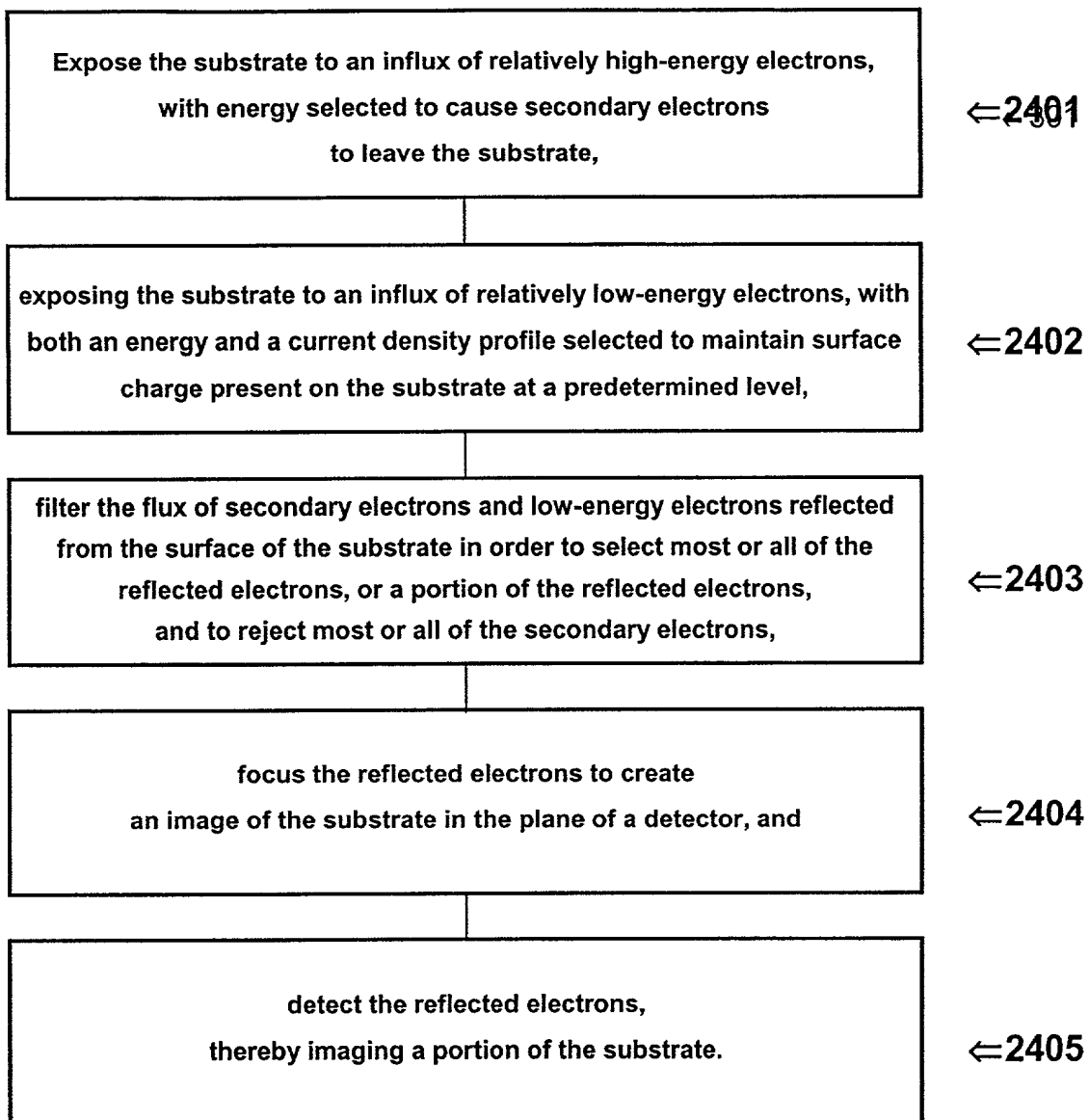
2302 

Figure 23



**Figure 24**



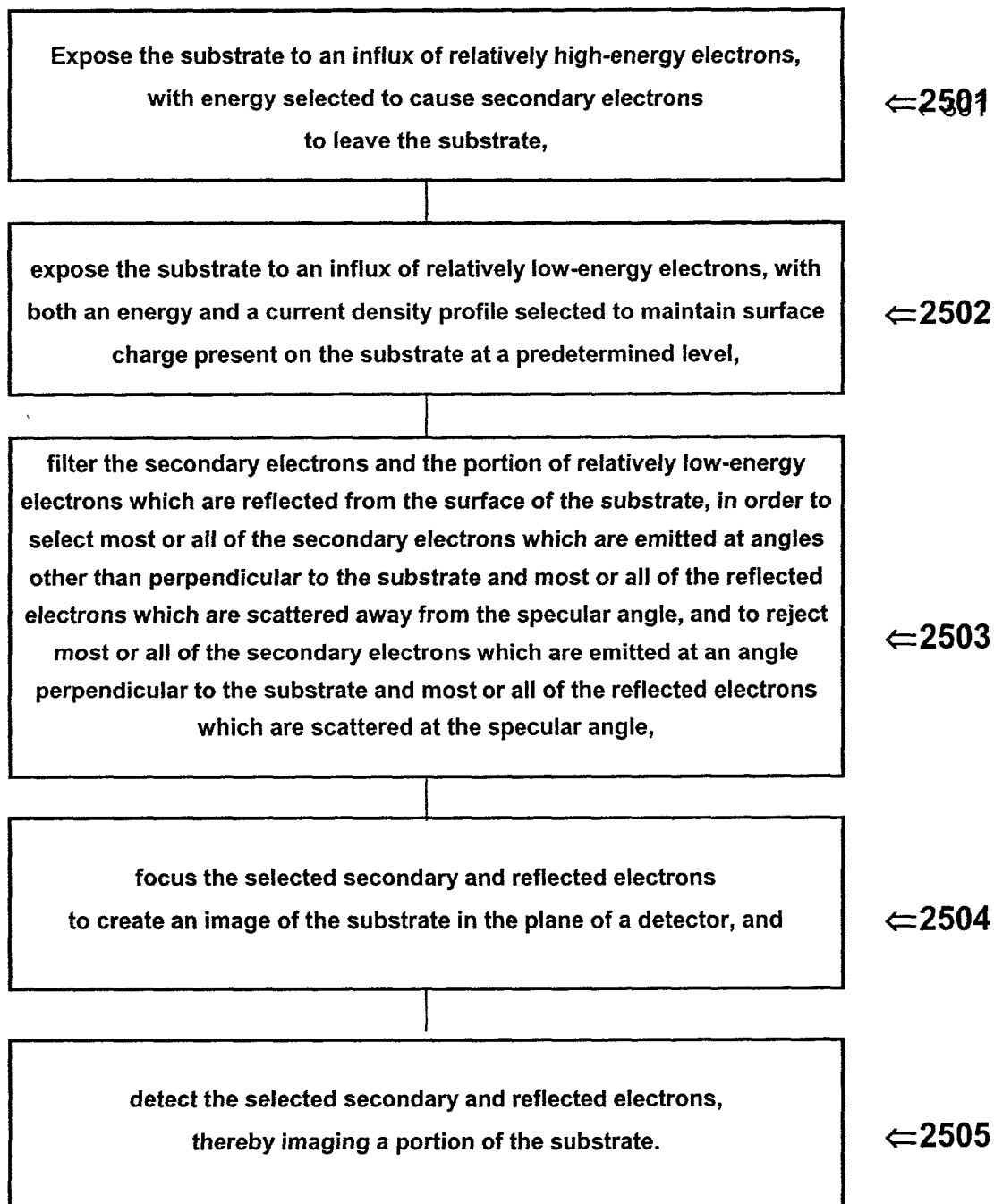


Figure 25